

## IN THE CLAIMS

Claims 1-24 (canceled)

25. (new) A coating for a substrate comprising a transparent  $\text{Si}_3\text{N}_4$  or  $\text{SiN}_x$  layer directly on the substrate, a semimetallic layer above the  $\text{Si}_3\text{N}_4$  or  $\text{SiN}_x$  layer and with a further  $\text{Si}_3\text{N}_4$  or  $\text{SiN}_x$  layer as well as with a dielectric oxide layer selected from the group consisting of  $\text{Al}_2\text{O}_3$ ,  $\text{SnO}$ ,  $\text{Nb}_2\text{O}_5$ ,  $\text{TiO}_2$  and  $\text{SiO}_2$ , wherein the dielectric oxide layer is disposed on the semimetallic layer and the further  $\text{Si}_3\text{N}_4$  layer on the dielectric oxide layer.

26. (new) The coating for a substrate as claimed in claim 25, wherein the semimetallic layer comprises a  $\text{CrN}$  layer.

27. (new) The coating for a substrate as claimed in claim 25, wherein a dielectric oxide layer is provided between the transparent  $\text{Si}_3\text{N}_4$  or  $\text{SiN}_x$  layer and the semimetallic layer.

28. (new) The coating for a substrate as claimed in claim 25, wherein  $x$  is a number smaller than  $4/3$ .

29. (new) The coating for a substrate as claimed in claim 26, wherein the semimetallic layer comprises  $\text{NiCrN}$  or  $\text{NiCrO}_x$ .

30. (new) A coating for a substrate as claimed in claim 25, wherein the transparent  $\text{Si}_3\text{N}_4$  or substoichiometric  $\text{SiN}_x$  layers have each a layer thickness of 20 to 120 nm.

31. (new) A coating for a substrate as claimed in claim 25, wherein the dielectric oxide layers have each a layer thickness of 4 to 120 nm.

32. (new) A coating for a substrate as claimed in claim 25, wherein the semimetallic NiCrN, CrN or NiCrO<sub>x</sub> layers have a layer thickness of 5 to 40 nm.

33. (new) A coating for a substrate as claimed in claim 25, wherein said substrate is glass.

34. (new) A coating for a substrate as claimed in claim 25, wherein said substrate is a synthetic material.

35. (new) A coating for a substrate as claimed in claim 25, further comprising additional layers comprising Cr, Ni or NiCr.